

Appl. No. 10/650,504  
Amdt. Dated March 15, 2007  
Reply to Office Action of December 15, 2006

Attorney Docket No. 81872.0052  
Customer No. 26021

do  
not  
enter  
3/23/07

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1-12. (Canceled)

13. (Currently amended): A ~~dry etching method~~ for producing a solar cell, ~~etching a surface of a substrate to be etched, said method comprising:~~

placing a substrate for a solar cell ~~to be etched~~ on an electrode inside a chamber; ~~wherein a part of said chamber is connected to a ground; and~~

~~covering said substrate to be etched with a plate between said part of said chamber and said electrode, wherein said plate is provided with a number of opening portions; and~~ [[,]]

forming textures on a surface of the substrate by using residues being chiefly composed of components of the substrate as an etching mask, wherein a distance between said substrate and a surface of said plate opposing said substrate ~~to be etched and said substrate to be etched~~ in a peripheral portion of said plate is set shorter than a distance between said substrate and said surface opposing said substrate ~~to be etched and said substrate to be etched~~ in a central portion of said plate.

14. (Currently amended): The ~~dry etching method~~ for producing a solar cell according to claim 13, wherein said textures are formed by dry etching method is a reactive ion etching method.

15-19. (Canceled)